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	Application No.	Applicant(s)	
	10/043,483	CHOI, WILLYS	
Notice of Allowability	Examiner	Art Unit	
	Daborah Chacko-Davis	1756	
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this or other appropriate communical IGHTS. This application is subjection	application. If not included ion will be mailed in due course. <b>Th</b>	<b>∃IS</b> itiative
1. $\square$ This communication is responsive to $02/09/2004$ .			
2. ☑ The allowed claim(s) is/are <u>1-30</u> .			
3. $igotimes$ The drawings filed on $02/09/2004$ are accepted by the Exa	aminer.		
4. ☐ Acknowledgment is made of a claim for foreign priority una) ☐ All b) ☐ Some* c) ☐ None of the:  1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority do	e been received. e been received in Application No		he
International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a repAENT of this application.	oly complying with the requirements	}
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>	nitted. Note the attached EXAMIN es reason(s) why the oath or decl	ER'S AMENDMENT or NOTICE OF áration is deficient.	Ξ
6. CORRECTED DRAWINGS ( as "replacement sheets") mu			
(a) ☐ including changes required by the Notice of Draftspers	son's Patent Drawing Review ( P	O-948) attached	
1)  hereto or 2)  to Paper No./Mail Date	<u>.</u>		
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the dra the header according to 37 CFR 1.1	awings in the front (not the back) of 21(d).	
<ol> <li>DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT</li> </ol>	osit of BIOLOGICAL MATERIA FOR THE DEPOSIT OF BIOLOG	L must be submitted. Note the GICAL MATERIAL.	
Attachment(s)  1. □ Notice of References Cited (PTO-892)  2. □ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. □ Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date  4. □ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summ Paper No./Mail 08), 7. ☑ Examiner's Ame	Date .	

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## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Stephen B. Ackerman on March 15, 2004.

The application has been amended as follows: Claim 2, at line 4, "TG" has been replaced with  $--T_g$  --.

Claim 13, at line 3, the term "Critical Dimension" has been replaced with the word --pitch--.

Claim 14, at line 7, before the words "first direction" the article "an" has been replaced with --a--.

Claim 21, at line 7, before the words "first direction" the article "an" has been replaced with --a--.

Claim 28, at line 7, before the words "first direction" the article "an" has been replaced with --a--.

The preceding amendments were made to overcome minor informalities.

2. The following is an examiner's statement of reasons for allowance: Claims 1-2, are allowable over the prior art or record (IBM Technical Disclosure Bulletin (NA8909149)) because the prior art fails to disclose a method of modifying a slope of

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sidewalls of openings in a layer of photoresist comprising mounting the substrate with the patterned layer of photoresist on a second surface of a hot plate positioned in an upwards-down position, and applying energy in the form of heat to the patterned layer of photoresist for a first period of time, discontinuing the energy in the form of heat to the patterned layer of photoresist for a second period of time, placing the hot plate in an upwards position, and creating a modified layer of photoresist having openings of modified slopes of sidewalls of said photoresist openings. Claims 3-30, are allowable over the prior art of record (IBM Technical Disclosure Bulletin (NA8909149)) because the prior art of record fails to disclose method of changing critical dimension in a photoresist layer comprising forming at least one patterned semiconductor material layer on the substrate and creating a patterned photoresist layer on the patterned semiconductor material layer, forming at least one opening through the photoresist layer, wherein the photoresist openings have sidewalls that intersect at an angle with the semiconductor material, and changing the angle of intersect in the sidewalls of the photoresist openings by raising the temperature of the patterned photoresist layer while placing the surface of the patterned layer of photoresist under an angle with a horizontal plane, said plane coinciding with the plane of the earth's surface.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571)272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dcd **%** March 15, 2004.

> MARK F. HUFF SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 1700